

First stages of nanoporous oxide growth on Ti in organic fluoride-containing electrolytes

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INTRODUCTION

- Electrochemical formation of self- ordered arrays of TiO₂ nanotubes → great interest due to their applications in sensors, dye sensitized solar cells, batteries, and even bio- implants.
 Benefits of electrochemically grown TiO₂ → fabrication of nanotube arrays of different shape, pore size, length, and wall thickness → controlling electrochemical parameters (potential, electrolyte composition and fluoride content, process duration, stirring...)
- Investigation of anodic film growth on Ti in organic electrolyte with different amounts of fluoride by electrochemical methods
- · Estimation of the chemical composition of the oxide surface
- Comparison of the model and experimental results

EXPERIMENTAL

 Electrochemical anodization in a potentiostatic regime – three-electrode configuration: pure Ti (99.9%. Goodfellow) as working electrode, Pt mesh counter electrode, Ag / AgCl / 3 M KCl reference electrode

- Electrolytes 0.6 M and 1.1 M $\rm H_2O$ in ethylene glycol with the addition of 0.01, 0.06, 0.1 and 0.2 M $\rm NH_4F$
- Electrochemical measurements Autolab PGSTAT30+FRA, GPES and FRA2 software (EcoChemie)
- Steady-state current vs. potential curves (potentiostatic mode)
- Electrochemical impedance spectra → range of potentials -0.1/5.0 V, frequency range 20 mHz – 20 kHz, ac amplitude 15 mV rms
- Chemical composition of the oxide film X-ray photoelectron spectroscopy (XPS)

RESULTS

Current vs. potential curves (Fig. 1)

Quasi-exponential increase of the current density with potential, constant currents reached for higher potentials

- Higher fluoride content → higher current densities and higher barrier film thicknesses at constant potential (as estimated from high-frequency capacitance)
- Oxide layer thickness → increases quasi-linearly with potential

Impedance spectra (Figs 2 and 3)

 two time constants – high-frequency capacitive and low-frequency pseudo-inductive migration of current carriers and recombination, capacitive behavior at low frequencies – modulation of film thickness (faradaic pseudocapacitance)

- the capacitance of the barrier layer decreases significantly with fluoride content, the
- product of ion migration resistance and current density increases slightly

X-ray photoelectron spectroscopy (Fig. 4)

Non- stoichiometric oxide, mainly Ti⁴⁺ and a smaller amount of Ti³⁺, with a certain degree of hydroxylation, thickness estimates agree with those from capacitance

DISCUSSION - Kinetic model of the process (Fig. 5)

- Growth of the barrier film → at the metal / film interface with oxidation of the metal and generation of oxygen vacancies
- · Consumption of these vacancies at the film / solution interface
- Film dissolution → chemical reaction, influenced by fluoride content
- Ejection of cations / generation of vacancies at the film/solution interface
- Recombination of cation and oxygen vacancies to recreate the perfect lattice



Fig. 5 A scheme of the processes of barrier layer formation and dissolution

Equation of current-potential curve and transfer function derived, first calculations with the model succesful in reproducing experimental behaviour (Fig.1a and 2a)

FUTURE STEPS

Determination of model parameters as depending on water / fluoride content
 Extension of the model to thicker films, nanopore initiation and growth



Fig. 1 a) Current vs. potential during anodization of Ti. Symbols – Experimental data, lines - calculated values according to the proposed model. b) barrier film thickness vs. potential in electrolytes with different fluoride content



Fig. 2 Impedance spectra of Ti at a) different potentials in an electrolyte with 0.06 M NH_4F , symbols – experimental data, lines – calculated values according to the proposed model, and b) at E = 4 V in electrolytes with different fluoride content





350 0.1 V 4500 2800 40000 sdo cps 35000 210 30000 Intensity. Intensity 2000 700 15000 10000 455 450 458 456 454 452 464 462 460 Binding energy / eV Binding energy / eV 4200 cps 280 OH ntensity Sitv 210 1400 534 530 534 532 530 532 h) Binding energy / eV Binding energy / eV

Fig. 4 Ti 2p XPS spectra a) and O1s spectra b) for TiO₂ films grown in an electrolyte with 0.06 M NH_4F and 1.1 M H_2O at different potentials

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